

PATENT

Attorney Docket No.: AMAT/8403/MASK/MASK-ETCH/ARNOLD S

Express Mail No.: EV 335470317 US

ABSTRACT OF THE DISCLOSURE

[0045] The present invention generally provides an improved pedestal for supporting a substrate. The pedestal has greatest application during a plasma etching process, such as for a quartz photomask, or "reticle." The pedestal defines a body, and a substrate support base along an upper surface of the body. The substrate support base has an outer edge, and an intermediate substrate support ridge for receiving and supporting the substrate. At least a portion of the substrate support base outside of the intermediate substrate support ridge is fabricated from a dielectric material. The purpose is to couple greater RF power through the reticle in order to enhance the plasma etching process.

250536_1